

	Hits	Search Text	DBs
36	69	((resist or photoresist) same (wafer or workpiece or substrate)) and ((first or initial) same (expos\$4 or illuminat\$4 or irradiat\$4)) and ((second near16 (expos\$4 or irradiat\$4 or illuminat\$4)) same (mask or photomask or reticle or optical or (direct near5 writ\$4) or maskless)) and pitch\$4 and linewidth and ((imprint\$4 or ion\$3beam or e\$2beam or (electron near4 beam)) near5 (system or apparatus or module))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
37	38	((resist or photoresist) same (wafer or workpiece or substrate)) and ((first or initial) same (expos\$4 or illuminat\$4 or irradiat\$4)) and ((second near16 (expos\$4 or irradiat\$4 or illuminat\$4)) same (mask or photomask or reticle or optical or (direct near5 writ\$4) or maskless)) and pitch\$4 and linewidth and ((imprint\$4 or ion\$3beam or e\$2beam or (electron near4 beam)) near5 (system or apparatus or module)) and interference	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB